

Abstract

An LPCVD apparatus comprising: a container for
accommodating an organometallic compound which serves as a
5 raw material; a heating means for heating the container and
vaporizing the organometallic compound to obtain a raw
material gas; a reactor for accommodating a substrate on
which a thin film being precipitated; an exhaust pump for
maintaining a low pressure atmosphere within the reactor;
10 and a trap provided on the upstream side of the exhaust pump
and cooling used raw material gas supplied from the reactor.
In the reactor, the trap is provided with honeycomb-
structure cylindrical fillers in a flowing passage through
which the used raw material flows. The LPCVD apparatus
15 according to the present invention enables recovery of a
larger amount of used raw material without reducing its
exhaust efficiency.